

*Amendments to the Specification*

[0001] This application is a continuation-in-part of U.S. Ser. No. 10/270,556, filed October 16, 2002, entitled “Advanced Illumination System For Use In Microlithography,” (now U.S. Patent No. 6,775,069 that issued August 10, 2004 Application Publication 2003/0076679 A1), which claims priority under 35 U.S.C. §119(e) to U.S. Provisional Patent Application No. 60/329,758, to Oskotsky et al., filed October 18, 2001, which are both incorporated herein by reference in their entireties.

[0002] This application is also a continuation-in-part of U.S. Ser. No. 10/166,062, to Oskotsky et al., entitled “Advanced Illumination System for Use in Microlithography,” filed June 11, 2002 (now U.S. Patent No. 6,813,003 that issued November 2, 2004 Application Publication No. 2003/0227609 A1), which is incorporated by reference herein in its entirety.

[0003] This application is related to U.S. Ser. No. 10/808,436, filed March 25, 2004, 10/\_\_\_\_\_, filed \_\_\_\_\_, (Atty. Doc. No. 1857.0700002) to Coston et al., which is incorporated by reference herein in its entirety.